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Please add the following claim:

29. A lithography system according to claim 3, wherein the resist coated on the substrate is chemically amplified resist. --

REMARKS

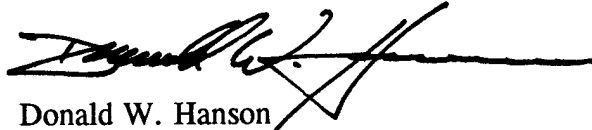
Claims 1-29 are now pending in this application.

The above amendments to the claims have been made to delete the multiple dependency of the claims and to put the application in better condition for examination. No new matter has been added.

In the event that any fees are due in connection with this paper, please charge our Deposit Account No. 01-2340.

Respectfully submitted,

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